

ABSTRACT OF THE DISCLOSURE

METHOD OF FORMING A PATTERN USING A POLARIZED RETICLE IN CONJUNCTION WITH POLARIZED LIGHT

Polarized reticles, photolithography systems utilizing a polarized reticle, and methods of using such a system are disclosed. A polarized reticle is formed having a reticle containing at least one first patterned region at least partially surrounded by at least one second patterned region. The first patterned region of the polarized reticle includes a polarized material and the second patterned region of the polarized reticle also includes a polarized material. Polarization directions of the polarized materials of the two regions are generally orthogonal to each other. When the polarized reticle is irradiated using linear polarized light having a selected polarization direction, the polarized materials on the two regions of the polarized reticle may be selectively used as a filter to enable exposing the different regions of the polarized reticle separately under optimal illumination conditions.

[FIG. 3A]